

SPI Plasma Prep III™



Tabletop plasma etcher/ashing system designed to work with a wide variety of sample materials and process gasses
just a click away... 2spi.com/plasmaprep3



SPI Supplies Division of **STRUCTURE PROBE, Inc.**

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SPI Supplies Plasma Prep III™

The Plasma Prep III is the latest member of our Plasma Prep family. The system incorporates solid-state technology, including an integrated vacuum gauge. As part of its low cost design, the system comes single gas inlet. The addition of the optional Process Control Module expands the system, and allows precise mixing of multiple gasses, as well as the ability to automatically shut the system down when the process is complete.

Typical Applications:

- Electron microscopy sample preparation
- Replace wet chemical etching
- Remove photo resist residue
- Remove organic contaminants
- Aperture cleaning
- Asbestos analysis
- Failure analysis

System Specifications:

- 13.56 MHz RF plasma
- Barrel design reaction chamber
- Adjustable power, from 1 to 100 watts
- Integrated vacuum gauge
- Size: 12" W x 15" D x 10.5" H
(31 cm W x 38 cm D x 27 cm H)
- Chamber size: 4" diameter x 6" deep
- CE Certified and RoHS Compliant

System Includes:

- Plasma Prep III
- Either Pyrex or quartz chamber
- Vacuum hose (NW 16)
- Power cord

Site Requirements:

- Process gas: 5 psig
- Vacuum pump
- Electrical Power: 100 V to 240 V, 50/60 Hz

Plasma Prep III shown with Process Controller



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